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PROCESSUS ELECTROCHIMIQUE

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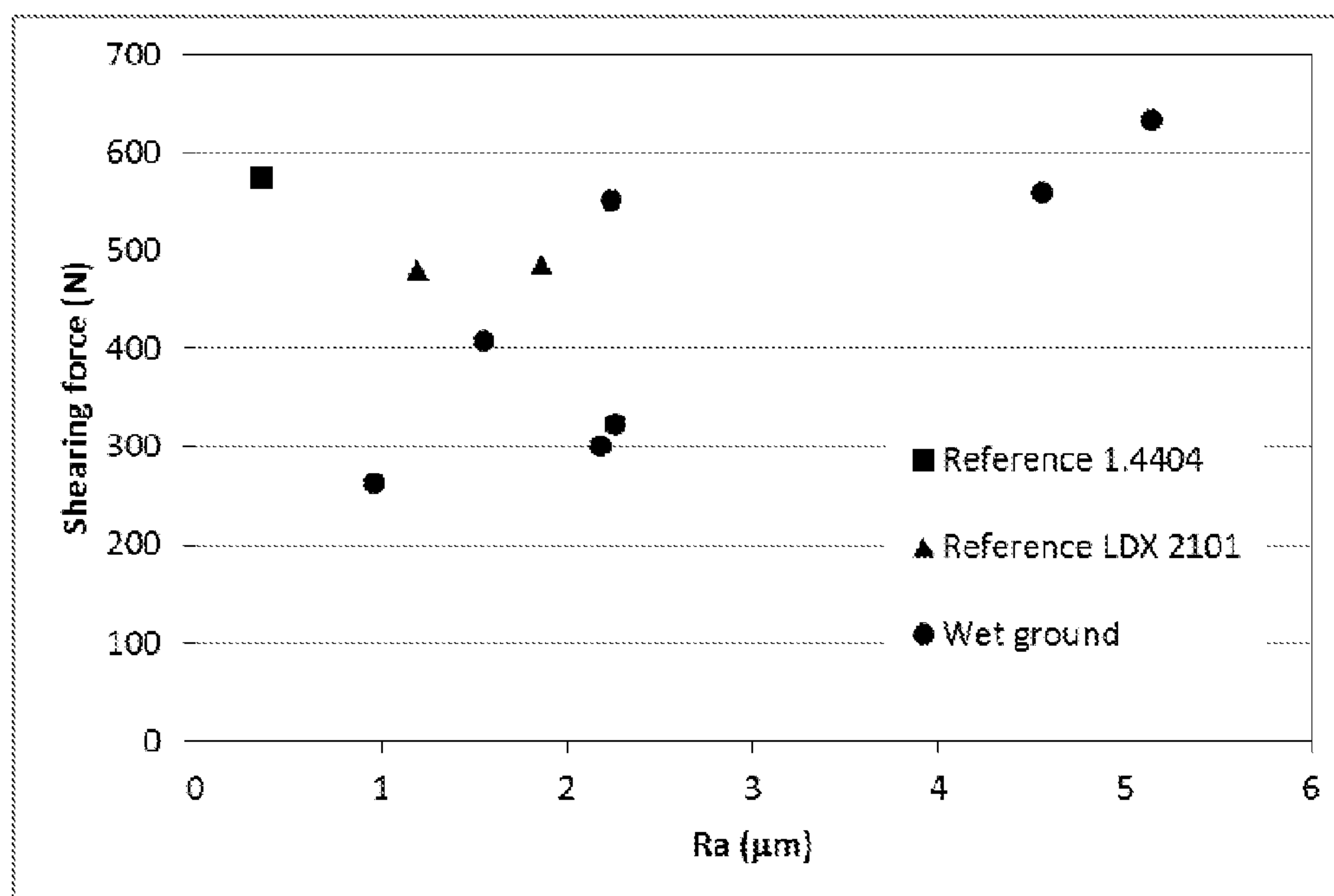


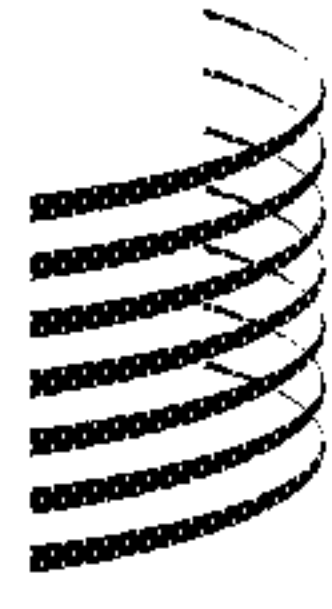
Fig. 1

(57) Abrégé/Abstract:

The invention relates to a method for manufacturing a plate material which is used in the electrochemical process of metal as a part of a cathode on which surface a metal is deposited. The surface roughness of the plate material for the adhesion between the metal deposit and the plate material is achieved with at least one treatment in a coil processing line.



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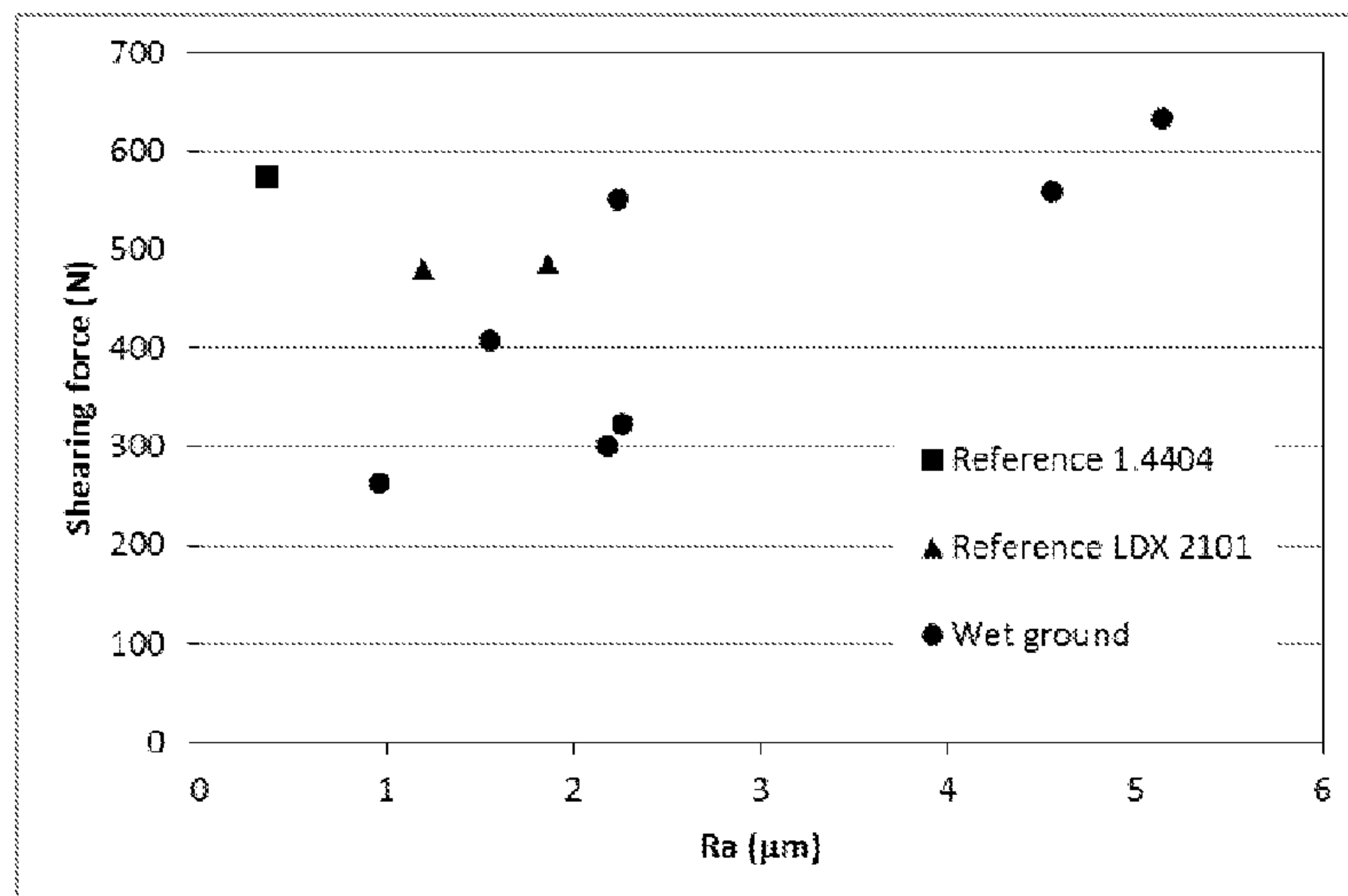


Fig. 1

(57) Abstract: The invention relates to a method for manufacturing a plate material which is used in the electrochemical process of metal as a part of a cathode on which surface a metal is deposited. The surface roughness of the plate material for the adhesion between the metal deposit and the plate material is achieved with at least one treatment in a coil processing line.

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METHOD FOR MANUFACTURING A PLATE MATERIAL FOR ELECTROCHEMICAL PROCESS

The present invention relates to a method for manufacturing a plate material
5 which is used in the electrochemical process of metal, such as electrorefining or electrowinning.

The surface roughness of a cathode plate material is an important parameter for the adhesion of electrochemically plated metals in the hydrometallurgical
10 industry. Experiences from the industry have shown that the surface needs to be rough enough to ensure adhesion and avoid prestripping of the plated metal, but on the other hand not too rough to prevent the adhesion force to be too high making the removal of the plated metal very difficult or damaging the plates in the stripping process. In the copper industry stainless steels have
15 been used as cathode plates both for electrorefining and for electrowinning. The preferred stainless steel grade for a cathode plates has been the grade EN 1.4404 (316L / UNS S31603) with a cold rolled surface 2B. This stainless steel grade contains typically 10 – 13 weight % nickel, which is an expensive component. Therefore, the copper industry is not only looking for more cost
20 efficient alternatives such as duplex stainless steels as cathode plates, but also more economical processes to manufacture a cathode plate.

An electrochemical process step is one of the final steps in processing of for instance metallic copper. In electrorefining copper anodes and cathodes are
25 positioned in an electrolytic solution that contains copper sulphate and sulphuric acid. An electric current is passed through the solution causing copper from the positively charged anode to be deposited on the negatively charged cathode. Electrowinning of copper is performed by a similar process, but the copper is removed from the solution, instead of the anode, and
30 deposited on the cathode. When an appropriate amount of copper has been deposited on the cathode, the cathode is removed from the solution and

stripped in order to remove the copper deposit from the surface of the cathode plate.

The US patent 7,807,029 relates to a permanent stainless steel cathode plate,
5 the cathode being composed of a low-nickel duplex steel or a lower grade “304”
steel, wherein at least one of the cathode surfaces has a surface roughness to
produce the adhesion necessary to allow operational adherence. The adhesion
is insufficiently strong to prevent the mechanical separation of the copper
deposit from the surface. However, the desired adhesion in the US patent
10 7,807,029 is only based on the predetermined adhesion characteristics, which
determines for the respective surface a surface roughness R_a within the range
of 0,6 – 2,5 micrometre. Any specific determination for adhesion on the surface
is not presented as well as the method for manufacturing a cathode plate.

15 The WO publication 2012/175803 describes a permanent cathode and a
method for treating the surface of a permanent cathode. In the method the
grain boundaries of the permanent cathode plate surface are treated chemically
or electrochemically to achieve the desired surface properties for the adhesion
of deposited metal on the surface and the stripping of metal from the surface.

20

Both the cited US patent 7,807,029 and the cited WO publication 2012/175803
focus the surface treatment to an individual and separate cathode plate to be
used as an electrode in electrowinning of electrorefining. These references do
not describe anything how the individual and separate cathode plate has been
25 produced.

The object of the present invention is to prevent some drawbacks of the prior
art and to achieve an improved method for manufacturing a plate material to be
used in the electrochemical process of metal, such as electrorefining or
30 electrowinning. The essential features of the present invention are enlisted in
the appended claims.

According to the present invention a plate material is used as a part of a cathode on which surface a metal is deposited in the electrochemical process of metal, such as electrefining or electrowinning. The plate material is manufactured in a coil processing line, such as a cold rolling process line, so
5 that the desired surface roughness for adhesion between the metal deposit and the plate material is achieved. The surface roughness of the plate to be used as a part of a cathode is made by at least one mechanical and/or chemical treatment in the coil processing line. The treatments for the desired surface roughness can be for instance one or more of the following treatments pattern
10 rolling, wet-grinding, dry-grinding, shot blasting, pickling, brushing, skin passing or any combination of these treatments.

The plate material to be treated in the coil processing line is advantageously a strip made of stainless steel. After the final treatment in the coil processing line
15 the plate material, a product received from the coil processing line, having the desired surface roughness is kept as a shape of plate, but can be advantageously treated to have a form of a coil. As a shape of a plate the material can be cut into the desired dimensions to be utilized as a part of a cathode on which surface a metal is deposited in an electrochemical process.
20 In the case the plate material is as a form of a coil, the plate material is essentially easy to transfer to a site where the electrochemical process of metal is carried out. The coiled plate material is then cut for a shape advantageous for the operation of the electrochemical process of metal.

25 The coil processing line in accordance with the invention advantageously contains the process steps such as annealing, chemical surface treatment, mechanical surface treatment, cold rolling. The chemical surface treatment can be for instance pickling. The mechanical treatment can be for instance grinding, wet-grinding or dry-grinding, brushing and shot blasting. The cold rolling can be
30 carried out for instance by pattern rolling. Any combinations of these process steps can be utilized in order to have a plate material with the desired surface roughness. According to one preferred embodiment of the invention the coil

processing line for the plate material consists of the treatments pre-annealing and pickling, cold rolling, grinding, final annealing and pickling.

The plate material treated with the invention is utilized as a part of a cathode in an electrochemical process of metal, where the metal to be deposited on the plate material is for instance copper, nickel or silver. The electrochemical process can be for instance electrorefining or electrowinning.

In order to achieve a desired surface roughness for a plate to be used in the electrochemical process of metal, the adhesion in the electrochemical process of metal is determined by measuring a shearing force required to detach the deposited metal between the surface of a plate and metal deposited on the surface of the plate. The shearing force is measured using a tool for use in a tensile testing machine. A specimen made of a plate material such as stainless steel is placed in the tool so that the specimen is movable, but tight enough so that a metal deposit on the surface of the specimen remains on the tool wall where the metal piece is fixed. The tool with the specimen is then placed in a tensile testing machine so that the specimen is pressed down, while the metal deposit is kept at a fixed position. The shearing force required to separate the metal deposit from the specimen is measured when the specimen is lowered.

The invention is described in more details referring to the following drawing, where

Fig. 1 shows one preferred embodiment of the invention, with copper as the metal to be deposited on the plate material, illustrating the correlation between the shearing force and the surface roughness R_a ,

Fig. 2 shows one preferred embodiment of the invention, with copper as the metal to be deposited on the plate material, illustrating the correlation between the shearing force and the surface roughness R_a in industrial scale.

30

The effects of a surface roughness and the chemical composition of the plate material to the shearing force between copper to be deposited and the plate to

be used in the electrochemical process of copper are determined on one hand using different plate materials and on another hand different surface roughness values on the plate surface. In order to compare whether a plate material itself makes a difference to the shearing force, plate specimens are ground to a similar surface roughness value. For the determination of the effects to shearing force caused by the surface roughness, different surface roughnesses are achieved for the specimens made of the same plate material. Further, the effect of the alignment of grooves achieved advantageously by grinding on the surface of the plate specimen is determined by achieving on the surface both grinding grooves which are parallel to the length of the specimen and grinding grooves which are essentially perpendicular to the length of the specimen.

The copper deposit on the surface of the plate specimen is achieved in an electrochemical cell where an electrolyte consisting of hydrated copper sulphate, sodium chloride, thiourea and sulphur acid is simulating the industrial-scale electrolyte in the copper electrefining. In the electrochemical cell a saturated calomel reference electrode (SCE) is used to register the potential during the operation, and a platinum mesh is served as a counter electrode. During the electrochemical process air is bubbled into the electrolyte to promote stirring. The electrochemical process will be stopped, when a desired amount of copper is deposited on the surface of the plate specimen.

The main element contents of the chemical compositions for the tested plate materials in weight % are in the following table 1:

	C %	Mn %	Cr %	Ni %	Mo %	N %	Cu %
A	0,020	-	17,2	10,1	2,1	-	-
B	0,030	5,0	21,5	1,5	0,30	0,22	0,30
C	0,020	-	22,0	5,7	3,1	0,17	-

Table 1

The alloy A represents an austenitic stainless steel of EN 1.4404 (316L / UNS S31603) which typically is used for a cathode plate and which contains in weight % less than 0,03 % carbon (C), less than 2 % manganese (Mn), 16,5 – 18,5 % chromium (Cr), 10 – 13 % nickel, 2 – 2,5 % molybdenum (Mo) and less than 0,10 % nitrogen (N).

The alloy B represents a duplex austenitic ferritic stainless steel of EN 1.4162 (LDX 2101/UNS32101) which typically contains in weight % less than 0,04 % carbon (C), 4 - 6 % manganese (Mn), 21 – 22 % chromium (Cr), 1,35 – 1,70 % nickel, 0,1 – 0,8 % molybdenum (Mo), 0,2 – 0,25 % nitrogen (N) and 0,1 – 0,8 copper (Cu).

The alloy C represents a duplex austenitic ferritic stainless steel of EN 1.4462 (2205/UNS32205) which typically contains in weight % less than 0,03 % carbon (C), less than 2 % manganese (Mn), 21 - 23 % chromium (Cr), 4,5 – 6,5 % nickel, 2,5 – 3,5 % molybdenum (Mo) and 0,10 – 0,22 % nitrogen (N).

For the determination of the correlation between the surface roughness and the shearing force in the alloys A – C, different surface roughness values are achieved by using different abrasive belts and using abrasive belts that have been more or less worn. Further, different surface roughnesses are achieved by dry grinding or wet grinding of the surface. Also shot blast and pickled surfaces are tested as well as a material which is skin passed in a coil processing line.

In accordance with the invention the surface roughness measurements for the surface roughness values R_a (roughness average) are performed with a surface roughness meter where the cut-off is set to 0,8 mm and the needle traversal speed to 0,5 mm/s for those specimens with the R_a value less than 2,26 micrometre. For the specimens having the R_a value higher than 2,26 micrometre the cut-off is set to 2,5 mm and the needle traversal speed to 1 mm/s.

Each plate specimen was set in the electrochemical cell in order to achieve a copper deposit on the surface of each plate specimen. Before starting the shearing process it was noticed that the interface between the deposited copper and the specimen shows that copper has a very good penetration into
5 very small topographic features of the specimen surface.

For the measurement of the adhesion by shearing force between the deposited copper and the plate surfaces the specimens with the deposited copper are set in a tool so that the specimen can be moved, but the deposited copper remains
10 at the fixed position. The tool is then set in the tensile testing machine, and the cathode plate specimen is moved for the measurement the required force to separate the copper deposit from the plate specimen.

The plate specimens with their surface roughness as well as the measured
15 shearing forces are listed in the following table 2 and in the Fig. 1 for the surface roughness R_a . Also the values of the reference material are listed in table 2. In the table 2 the term "worn belt" means an abrasive belt which was utilized for the grinding treatment at least once before the actual treatment, while the term "new belt" means an abrasive belt which was not used for the
20 treatment in accordance with the invention before the actual treatment.

Test specimen	Alloy	Surface roughness R_a (μm)	Shearing force (N)
Reference surface (dry-ground)	A	0,36	574,8
Reference surface (dry-ground)	B	1,87	487,5
Reference surface (dry-ground)	B	1,2	480,6
Shot blast and pickled	B	2,89	655,8
Wet ground test 1 worn belt	B	0,96	262,8
Wet ground test 1 new belt	B	2,24	551,5
Wet ground test 2 new belt	B	1,55	407,5
Wet ground test 3 worn belt end	B	5,15	633,3
Wet ground test 3 new belt end	B	2,26	323,9

Wet ground test 3 worn belt start	B	4,56	560,0
Wet ground test 3 new belt start	B	2,18	301,0

Table 2

In the table 2 the results are based on three tests where the surface roughness is achieved by wet-grinding and one test where the surface roughness is achieved by the combination of shot-blasting and pickling. It is noticed that the adhesion measured by shearing force increases when the surface roughness values are increasing. An essentially linear trend can be seen for the wet ground surfaces. The shearing force measured between the plate and copper deposited on the surface of the plate is adjusted by the surface roughness of the plate, and as shown in Fig. 1 the shearing force is directly proportional to the surface roughness of the plate when the surface roughness of the plate is achieved by grinding. The highest shearing force value was measured for the specimen, which was treated as a combination of shot-blasting and pickling, first by shot blasting and then by pickling. Further, it was also noticed from the interface between the copper deposit and the stainless steel surface that the copper deposit has good penetration into very small topographic features of the stainless steel surface. Therefore, the surface roughness R_a 0,7 – 5,5 micrometre, preferably 0,7 – 2,5 micrometre, is sufficient for the desired adhesion between copper deposit and the stainless steel surface. Thus the shearing force is 250 - 800 N, preferably 250 – 650 N.

The connection between the surface roughness and the shearing force was also tested in the industrial scale, and the results are given in the table 3 and respectively in the Fig. 2 for the alloy B.

Specimen	Surface roughness R_a (μm)	Shearing force (N)
1	0,92	302
2	1,01	397
3	1,1	509
4	0,99	409

5	1,25	521
6	1,35	509
7	1,31	656
8	1,33	507
9	1,18	505
10	1,18	506
11	1,12	516
12	1,09	474
13	1	521
14	1,18	492
15	0,89	370
16	1,27	624

Table 3

The test results in the table 3 and in the Fig. 2 show that the surface roughness and the shearing force have a linear dependency to each other. Further, the results for the adhesion measured by shearing forces are essentially at the same ranges as the values for the shearing forces in the laboratory scale.

CLAIMS

- 1 Method for manufacturing a plate material which is used in the electrochemical process of metal as a part of a cathode on which surface a
5 metal is deposited, **characterized** in that the surface roughness of the plate material for the adhesion between the metal deposit and the plate material is achieved for the product received from the cold rolling process line with at least one treatment in a cold rolling process line.
- 10 2. Method according to the claim 1, **characterized** in that the surface roughness of the plate material is achieved mechanically.
3. Method according to the claim 1 or 2, **characterized** in that the surface roughness of the plate material is achieved by wet-grinding.
- 15 4. Method according to the claim 1 or 2, **characterized** in that the surface roughness of the plate material is achieved by dry-grinding.
5. Method according to the claim 1 or 2, **characterized** in that the surface
20 roughness of the plate material is achieved by shot blasting.
6. Method according to the claim 1 or 2, **characterized** in that the surface roughness of the plate material is achieved by brushing.
- 25 7. Method according to the claim 1 or 2, **characterized** in that the surface roughness of the plate material is achieved by pattern rolling.
8. Method according to the claim 1, **characterized** in that the surface roughness of the plate material is achieved chemically.

9. Method according to the claim 1, **characterized** in that the surface roughness of the plate material is achieved mechanically and chemically.

10. Method according to the claim 9, **characterized** in that the surface
5 roughness of the plate material is achieved by shot blasting and pickling.

11. Method according to any of the claims 1 - 10, **characterized** in that the surface roughness of the plate material is achieved by a combination of the treatments.

10

12. Method according to any of the preceding claims 1 - 11, **characterized** in that the surface roughness of the plate material by roughness average R_a is 0,7 – 5,5 micrometre, preferably 0,7 – 2,5 micrometre.

15 13. Method according to any of the preceding claims 1 - 11, **characterized** in that the shearing force of the plate material is 250 - 800 N, preferably 250 – 650 N.

14. Method according to any of the preceding claims 1 - 13, **characterized** in
20 that the plate material is for electrochemical process of copper.

15. Method according to the claim 14, **characterized** in that the plate material is for electrorefining of copper.

25 16. Method according to the claim 14, **characterized** in that that the plate material is for electrowinning of copper.

17. Method according to any of the preceding claims 1 - 13, **characterized** in that the plate material is for electrochemical process of silver.

30

18. Method according to the claim 17, **characterized** in that the plate material is for electrorefining of silver.

19. Method according to the claim 17, **characterized** in that that the plate
5 material is for electrowinning of silver.

20. Method according to any of the preceding claims 1 - 13, **characterized** in that the plate material is for electrochemical process of nickel.

10 21. Method according to the claim 20, **characterized** in that the plate material is for electrorefining of nickel.

22. Method according to the claim 20, **characterized** in that that the plate material is for electrowinning of nickel.

15

23. Method according to any of the preceding claims, **characterized** in that the plate material as a product from a coil processing line is made of an austenitic stainless steel which contains in weight % less than 0,03 % carbon (C), less than 2 % manganese (Mn), 16,5 – 18,5 % chromium (Cr), 10 – 13 % nickel, 2 –
20 2,5 % molybdenum (Mo) and less than 0,10 % nitrogen (N).

24. Method according to any of the preceding claims 1 -22, **characterized** in that the plate material as a product from a coil processing line is made of a duplex austenitic ferritic stainless steel which contains in weight % less than
25 0,04 % carbon (C), 4 - 6 % manganese (Mn), 21 – 22 % chromium (Cr), 1,35 – 1,70 % nickel, 0,1 – 0,8 % molybdenum (Mo), 0,2 – 0,25 % nitrogen (N) and 0,1 – 0,8 copper (Cu).

25. Method according to any of the preceding claims 1 - 22, **characterized** in
30 that the plate material as a product from a coil processing line is made of a duplex austenitic ferritic stainless steel which contains in weight % less than

0,03 % carbon (C), less than 2 % manganese (Mn), 21 - 23 % chromium (Cr),
4,5 – 6,5 % nickel, 2,5 – 3,5 % molybdenum (Mo) and 0,10 – 0,22 % nitrogen
(N).

5 26. Method according to any of the claims 1 - 25, **characterized** in that the
plate material is produced in the form of a coil.

27. Method according to any of the claims 1 - 25, **characterized** in that the
plate material is produced in the form of a plate.

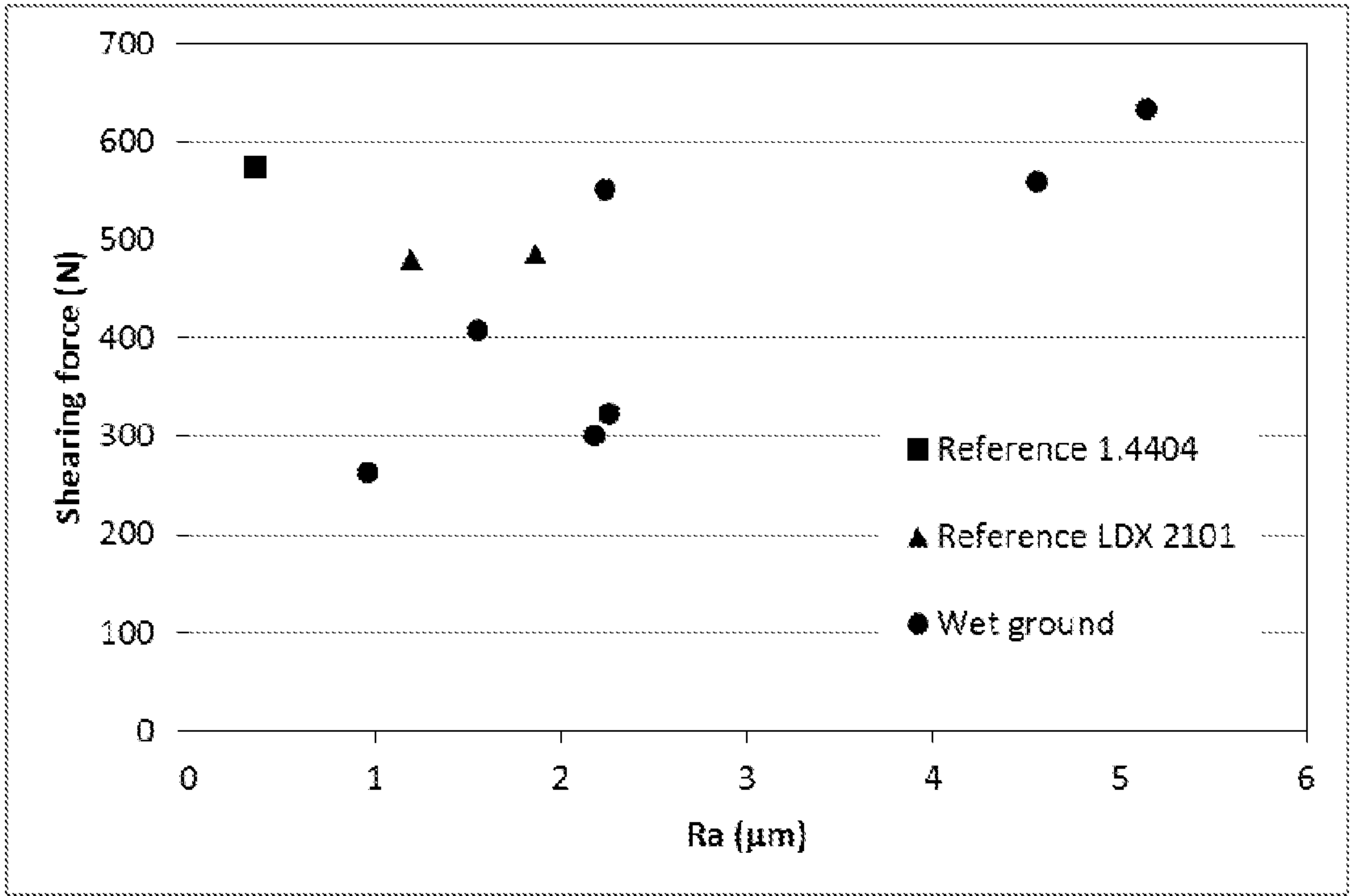


Fig. 1

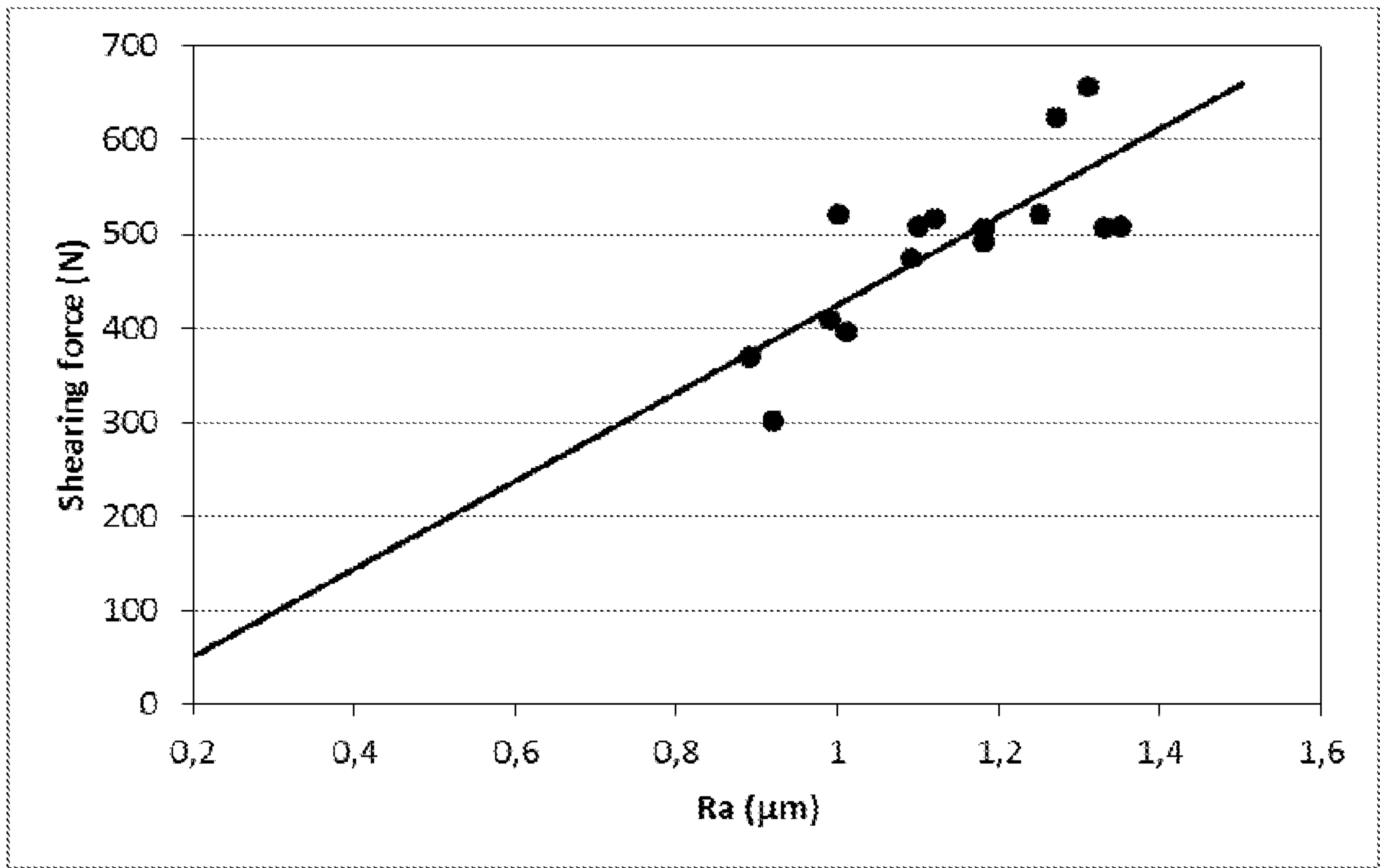


Fig. 2

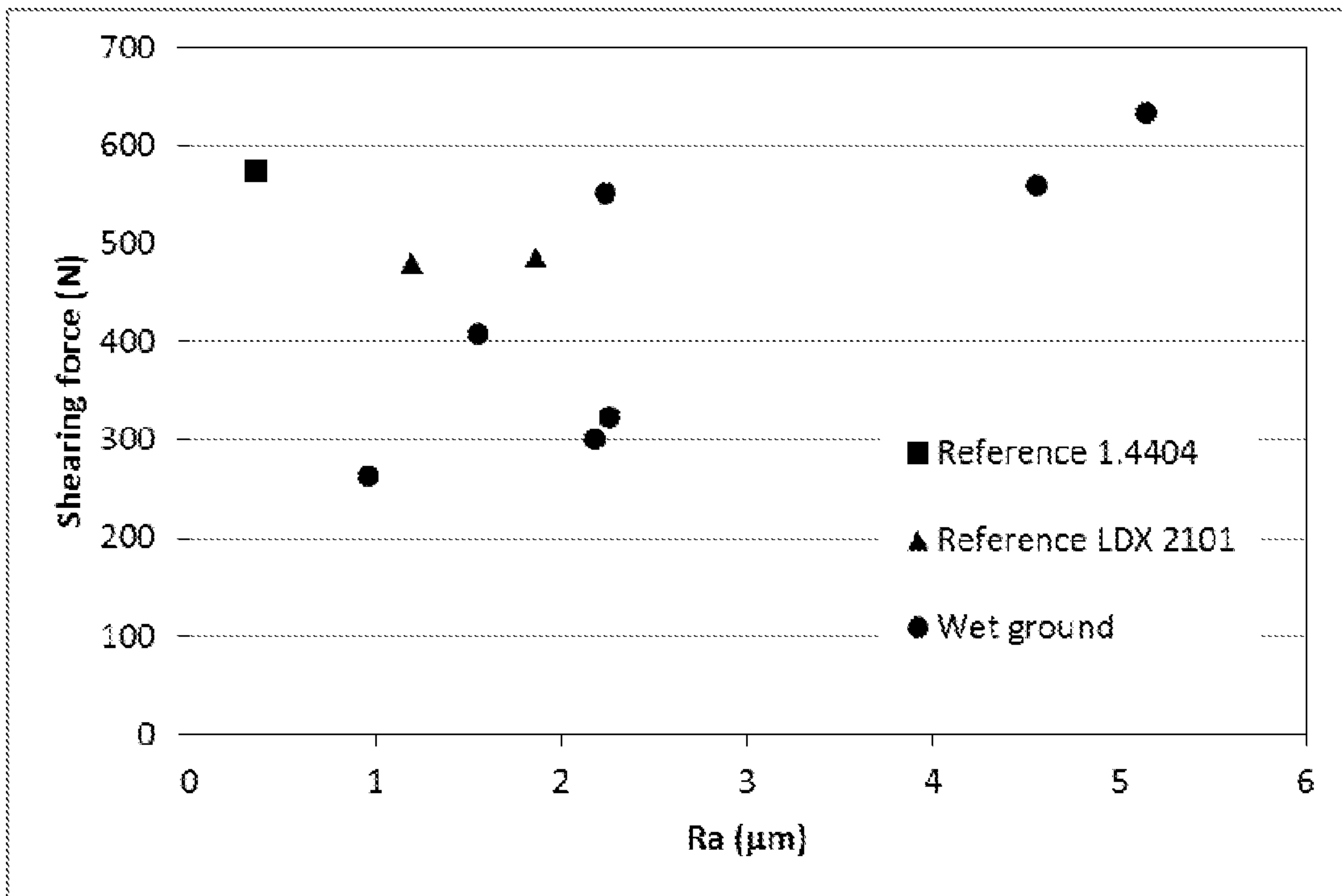


Fig. 1